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	Applicant Uemura KENSUKE et al.	
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**U.S. PATENT DOCUMENTS**

Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

**FOREIGN PATENT DOCUMENTS**

		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No

**OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

<i>Joe</i>	<i>Joe</i>	G. E. Ozur and D.I. Proskurovsky "Generation of Low Energy Electron Beam in the Diode With Plasma Anode", Proc. XIV Intern. Symp. on Discharges and Electric Insulation in Vacuum, Santa Fe, 1990, pp. 665-670.
<i>Joe</i>		N. A. Nochovnaya, V. A. Shulov, D. I. Proskurovsky, and V P. Rotshtein, "Modification of Titanium Alloy Parts Properties by Intensive Current Electron Beams", Proc. 11th Intern. Conf. on High Power Particle Beams (BEAMS'96), Prague, 1996, v.2, pp.813-816. —
<i>Joe</i>		N. A. Nochovnaya, V A. Shulov, V P. Rotshtein, A. B. Markov, D. S. Nazarov, G. E. Ozur, and D. I. Proskurovsky, "Modification of the Structure and Properties of Titanium Alloys by Low-Energy, High-Current Electron Beams", Proc. of 5th Intern. Conf. on Electron Beam Technologies (EBT'97), Varna, 1997, pp. 215-220. —
<i>Joe</i>		D. S. Nazarov, G. E. Ozur, and D. I. Proskurovsky "Production of Low-Energy High-Current Electron Beams in a Reflected-Discharge Plasma-Anode Gun", Proc. 11th IEEE Intern. Pulsed Power Conference, Baltimore, 1997, v.2, pp.1335-1340. —
<i>Joe</i>		D. I. Proskurovsky, V P. Rotshtein, G. E. Ozur, A. B. Markov D. S. Nazarov, V A. Shulov, Yu. F. Ivanov, and R. G. Buchheit, "Pulsed Electron-Beam Technology for Surface Modification of Metallic Materials", J. Vac. Sci. Technol. A 16(4), 1998, pp. 2480-2488. —

EXAMINER

*John Wilson*

DATE CONSIDERED

*6/24/03*

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